IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re f	Patent Application of)	
Kazud	NISHI et al.)	ATTN: New Applications
Based	d On: JP 2003-002667	_)	
Filed:	January 8, 2003)	
For:	SEMICONDUCTOR DEVICE)	
	AND METHOD OF)	
	MANUFACTURING THEREOF)	

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

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In accordance with the provisions of 37 C.F.R. 1.56 and 37 C.F.R. 1.97-1.99, Applicant submits herewith a Form PTO-1449 listing references known to Applicant and requests that these references be made of record in the above identified application. Copies of the references listed are submitted herewith in accordance with 37 C.F.R. 1.98(a). Copies of U.S. patents and U.S. publications are not enclosed in accordance with the Notice published in the Official Gazette on August 5, 2003 entitled *Information Disclosure Statements May Be Filed Without Copies of U.S. Patents and Published Applications in Patent Applications filed after June 30, 2003*, which waives the requirement under 37 CFR 1.98(a)(2)(i) for submitting a copy of each cited U.S. patent and each U.S. publication.

U.S. Patent Nos. 5,501,989; 5,589,694 and 5,744,822 are in the family of Japanese Patent Laid-Open No. 06-275808.

The Commissioner is hereby authorized to charge fees under 37 C.F.R. §§1.16, 1.17, 1.20(a), 1.20(b), 1.20(c), and 1.20(d) (except the Issue Fee) which may be required now or hereafter, or credit any overpayment to Deposit Account No. 50-2280. A duplicate copy of this sheet is attached.

- --- Respectfully submitted,

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Approved for use through 10/31/2002. OMB 0651-0031

U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Complete if Known Substitute for form 1449A/PTO Application Number INFORMATION DISCLOSURE January 2, 2004 Filing Date STATEMENT BY APPLICANT Kazuo NISHI et al. First Named Inventor (use as many sheets as necessary) Group Art Unit Examiner Name 1 of 1 Attorney Docket Number Sheet 0756-7243

		-		U.S. PATENT DOCUMEN	rs	
Examiner Initials	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited	Date of Publication of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number Kind Code ² (if known)		Document	MM-DD-YYYY	
		5,501,989		Takayama et al.	03/26/1996	"
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Examiner Initials	Cite No. ¹	Foreign Patent Document Kind Code ⁵			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Office ³ Number ⁴ (if known)						
		JР	06-275808			09/30/1994		Abst.
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Examiner Date
Signature Considered

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

DIALOG(R)File 352:Derwent WPI

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Image available

WPI Acc No: 1994-352764/199444

Related WPI Acc No: 1994-352761; 1994-352762; 1994-352763; 2001-106018;

2001-106199

XRAM Acc No: C94-160607 XRPX Acc No: N94-277001

Semiconductor circuit mfr. - by coating catalyst element on amorphous silicon@ film which promotes crystallisation with different density in

active region of TFT and intrinsic region of thin film diode

Patent Assignee: SEMICONDUCTOR ENERGY LAB (SEME)

Inventor: TAKAYAMA T; TAKEMURA Y

Number of Countries: 002 Number of Patents: 004

Patent Family:

Patent No	Kind	Date	Applicat No	Kind	Date V	Veek	
JP 6275808	Α	19940930	JP 9386747	Α	19930322	199444	В
US 5501989	Α	19960326	US 94216107	Α	19940321	199618	
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Priority Applications (No Type Date): JP 9386747 A 19930322; JP 9386744 A 19930322; JP 9386745 A 19930322; JP 9386746 A 19930322

Patent Details:

Patent No	Kind Lan Pg	Main IPC	Filing Notes
JP 6275808	Α	8 H01L-027/146	
US 5501989) A	23 H01L-021/335	;
US 5589694	A	23 H01L-029/78	Div ex application US 94216107
			Div ex patent US 5501989
US 5744822	2 A	22 H01L-021/20	Div ex application US 94216107
			Cont of application US 95483048
			Div ex patent US 5501989

Abstract (Basic): JP 6275808 A

The manufacturing method semiconductor circuit forms a semiconductor film on a substrate (1) which consist of at least one TFD and TFT. The semiconductor film forms the active region of TFT as well as intrinsic region (17) of TFD. The semiconductor circuit is featured by the density of catalyser elements which promotes crystallisation in the active region of TFT and intrinsic region of TFD.

USE/ADVANTAGE - For use in image sensor. Processes substrate with large area at one stretch. Reduces manufacturing cost.

Dwg.1/4

Title Terms: SEMICONDUCTOR; CIRCUIT; MANUFACTURE; COATING; CATALYST; ELEMENT; AMORPHOUS; SILICON; FILM; PROMOTE; CRYSTAL; DENSITY; ACTIVE; REGION; TFT; INTRINSIC; REGION; THIN; FILM; DIODE Derwent Class: L03; U11; U13; U14

International Patent Class (Main): H01L-021/20; H01L-021/335; H01L-027/146; H01L-029/78

International Patent Class (Additional): H01L-021/336; H01L-021/84; H01L-027/092; H01L-027/108; H01L-029/04; H01L-029/76; H01L-029/784 File Segment: CPI; EPI